

# **More than protection: the function of TiO<sub>2</sub> interlayers in hematite functionalized Si Photoanode**

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## EXPERIMENTAL METHODS

### *Synthesis and photo-electrochemical Characterization of functionalized n-Si photoelectrodes*

***n-Si MWs synthesis:*** A well-documented metal-assisted electroless wet chemical etching (MACE) method was used to synthesis n-Si microwires (n-Si MWs) as described by Peng *et al.* <sup>1, 2</sup>. A n-type Si (100) with resistivity (1-10 ohm-cm) were purchased from Siegert Wafer- Germany. The n-Si wafer was sliced into 2×2 cm<sup>2</sup> pieces. These small n-Si pieces were ultrasonically cleaned in acetone, followed by isopropanol inside a fume hood. The n-Si pieces were then immersed in HF to etch any nascent oxide layer for 30-45 seconds and then immediately rinsed with water followed by drying in a dry nitrogen stream.

Two different electrolyte solutions were prepared for the synthesis of n-Si MWs. An electrolyte solution (E1) comprised of 4.6 M HF and 0.02 M AgNO<sub>3</sub>. A second electrolyte solution (E2) comprised of 4.6 M HF and 0.02 M H<sub>2</sub>O<sub>2</sub>. HF was handled with recommended protective gear and under the fume hood. Cleaned n-Si pieces were first immersed in E1 for two minutes, to deposit Ag nanoparticles uniformly. These Ag nanoparticles coated n-Si pieces were then transferred into E2 and etched for 15 minutes. During MACE, a greenish-black silver dendritic debris is formed on top of n-Si MWs, which is removed by rinsing the silicon in water - HNO<sub>3</sub> solution (3:1 in volume).

***TiO<sub>2</sub> sol-gel synthesis:*** The sol-gel coating procedure resulted in a mesoporous TiO<sub>2</sub> layer due to the well-known block co-polymer sol-gel assisted evaporation induced self-assembly (EISA) process<sup>3, 4</sup>. Here, the block-co-polymer Pluronic P123 acts as a templating agent, while titanium (IV) butoxide acts as the inorganic TiO<sub>2</sub> precursor. This led to spherical micelles, which upon aging and annealing resulted in the mesoporous structure. Figure SI 1 shows the SEM image of mesoporous TiO<sub>2</sub> (mp-TiO<sub>2</sub>) coated on the planar n-Si substrate. For a more detailed

description, see for example <sup>5</sup>.

The TiO<sub>2</sub> sol was prepared from Titanium (IV) butoxide, HCl (35.5%), Pluronic P123, and 1-butanol, in the molar ratio of 1:2:0.103:9. All chemicals were purchased from Sigma Aldrich-Sweden. First, the Titanium (IV) butoxide and HCl (35.5%) were mixed in a vial and magnetically stirred for 1 hour. Pluronic P123 and 2-butanol were mixed in a separate vial to be then combined with the Titanium mixture vigorously stirred for 24 hours. The TiO<sub>2</sub> sol obtained after 24 hours was then kept in the dark until further use.

***TiO<sub>2</sub> coating on n-Si MWs:*** A spin-coating technique was employed to deposit a thin layer of TiO<sub>2</sub> onto n-Si MWs. Three cycles of 30 seconds each was programmed in a spin coater to rotate at 4000 rpm, and 1 ml of TiO<sub>2</sub> sol is dispensed on the n-Si MWs (2×2 cm<sup>2</sup>). The TiO<sub>2</sub> coated n-Si MWs substrates were then kept on a platform equipped with a water bath inside a closed airtight chamber for 24 hours and under ambient conditions. The moisture exposed TiO<sub>2</sub> samples were annealed at 380<sup>0</sup> C in a nitrogen environment for two hours to yield the n-Si MWs/TiO<sub>2</sub> photoelectrode substrate.

***Hematite deposition on n-Si MWs/TiO<sub>2</sub>:*** The α-Fe<sub>2</sub>O<sub>3</sub> nanorods on the n-Si MWs/TiO<sub>2</sub> structures were grown by the hydrothermal method as described by Vayssieres *et al.* <sup>6,7</sup> In brief, 0.15 M ferric chloride and 1 M sodium nitrate solutions were adjusted to pH 1.2 by dropwise addition of HCl. The n-Si MWs/TiO<sub>2</sub> substrates were soaked in this solution for 12 hours and kept under dry conditions in an autoclave at a constant temperature of 100°C. The n-Si MWs/TiO<sub>2</sub>/α-Fe<sub>2</sub>O<sub>3</sub> photoelectrodes were then rinsed with distilled water and ethanol followed by an annealing step at 380°C in a nitrogen environment for two hours.

***Photo-electrochemistry:*** All the potential-current (linear sweep voltammetry-LSV) experiments were performed in an airtight photo-electrochemical cell equipped with a quartz

window. The chronoamperometric and photogenerated gas-evolution measurements were performed in a gas-tight three-electrode quartz cell from Pine Instruments, Durham-USA, equipped with an Ag/AgCl reference electrode and a platinum counter electrode. A solar simulator from Newport- 94043A, equipped with 450W Xenon lamp and air-mass 1.5 filter and a potentiostat from Metrohm Autolab (PGSTAT302N) was used to illuminate our photoelectrodes and perform the electrochemical measurements, respectively. All the photoelectrodes were illuminated at one sun condition with a power density of 100 mW/cm<sup>2</sup>.

The linear sweep voltammetry was recorded at a scan rate of 20 mV/s with respect to an Ag/AgCl reference electrode and is reported in the main article as reversible hydrogen electrode potentials ( $V_{RHE}$ ) using equation Eq. S1

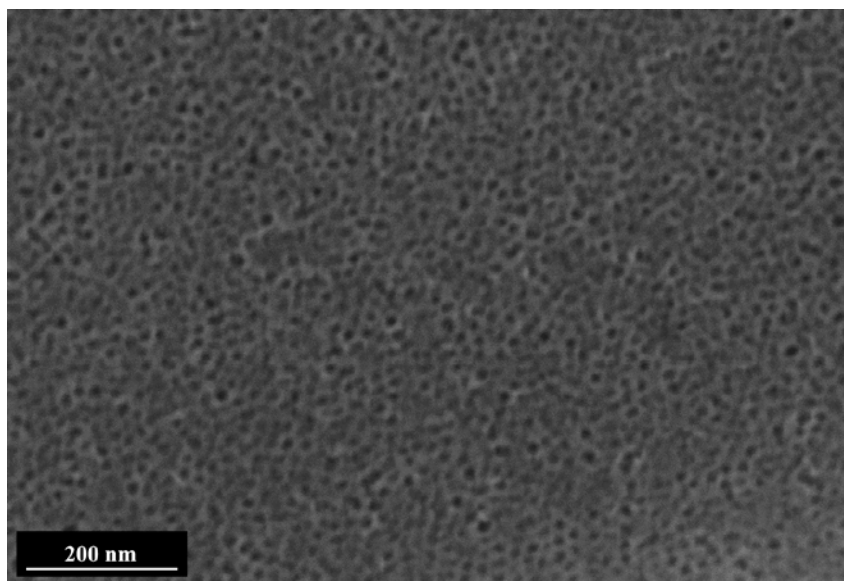
$$V_{RHE} = V_{Ag/AgCl} + 0.1976 + (0.059 \times pH) \quad \text{Eq. S1}$$

The transient photocurrent responses for the functionalized n-Si MWs photoanodes were recorded in a two-electrode mode using an IviumStat-XRi potentiostat.

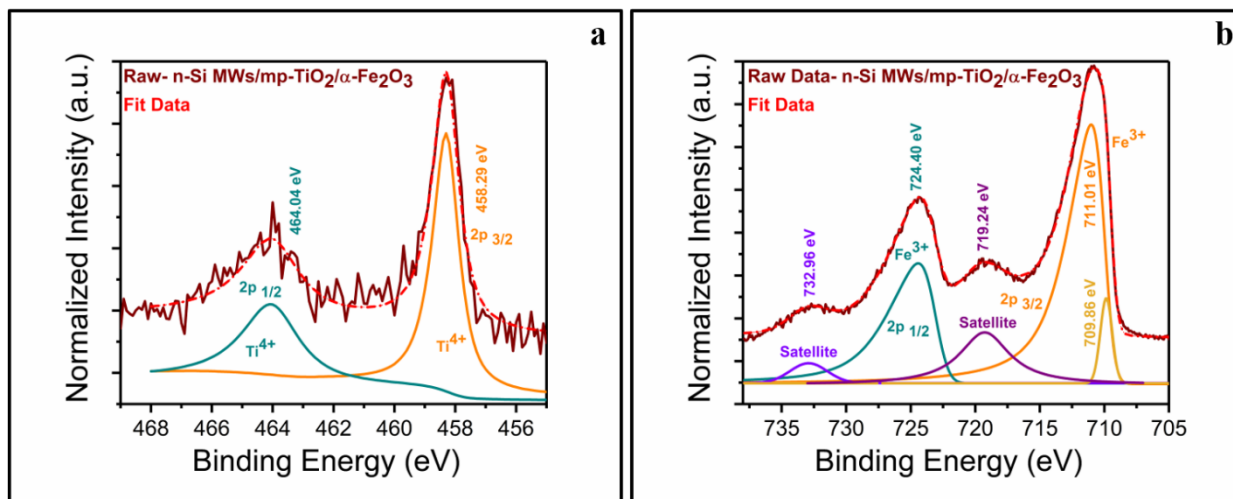
The photogenerated gases were measured by gas chromatography using a GC-8AIT gas chromatograph with a TCD detector (Schimadzu Scientific Instruments, Columbia, USA). 100  $\mu$ l aliquots from the headspace of the photo-electrochemical cell were taken at regular intervals and analyzed in the GC-8AIT.

**X-ray spectroscopy:** The X-ray absorption and emission spectroscopy (XAS-XES) was carried out on beamline ID26 of the European Synchrotron radiation facility. A schematic view of the optics and the experimental set up is presented elsewhere.<sup>8, 9</sup> The high-energy resolution fluorescence detected X-ray absorption near edge structure (HERFD-XANES) and emission spectroscopies were performed at the Ti (K- $\alpha$  and  $\beta$  fluorescence line ) and Fe K- $\beta$  fluorescence line. A Si <311> double crystal monochromator was used to tune the incident beam at the Ti K-

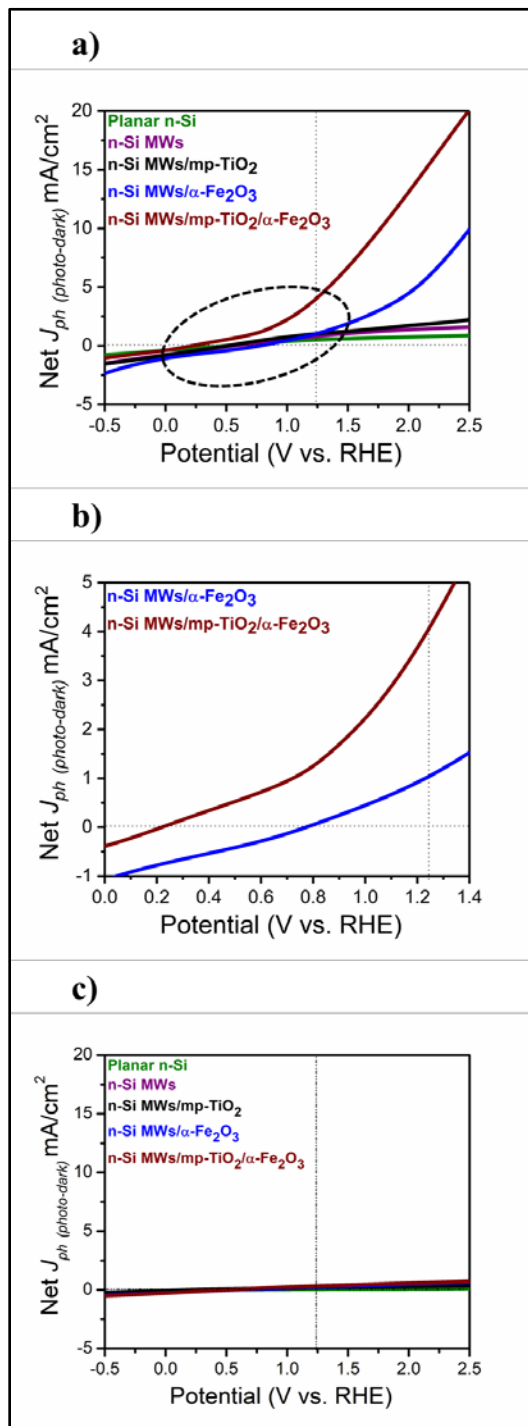
edge. The incident X-ray energy was calibrated using Ti and Fe foils. The X-ray beam was focused on the sample and guarded by slits with size 0.7 mm in the horizontal and 0.2 mm in the vertical dimension. Higher harmonics were suppressed by total reflection using three Si mirrors at 2.5 mrad. The high-energy resolution fluorescence detected X-ray absorption near edge structure (HERFD-XANES) spectra were recorded at the maximum of the Ti and Fe  $K\alpha_1$  line. The fluorescence energy was selected by two Ge (400), five Ge(331), and five Ge(620) for Ti  $K\beta$ , and Fe  $K\beta$  bent crystal analyzer ( $R=1\text{m}$ ,  $r=100\text{ mm}$ ), respectively, arranged in Rowland geometry.<sup>8, 10</sup> The X-ray photons selected by the crystal analyzers were focused onto an avalanche photodiode. The samples were placed into a fluorescence geometry, where the incident beam and the central crystal analyzer are at  $45^\circ$  with respect to the sample surface standard and at  $90^\circ$  angles between the incident beam and the central crystal analyzer. All HERFD-XANES and XES spectra reported here were normalized with respect to the total spectral area. Fluorescence-detected absorption spectra may show spectral distortions because of incident beam self-absorption or over-absorption effects.<sup>11</sup> One consequence of self-absorption may be an increased pre-edge spectral intensity. We did not correct the spectra for self-absorption but ensured that artefacts do not affect the conclusions drawn here.



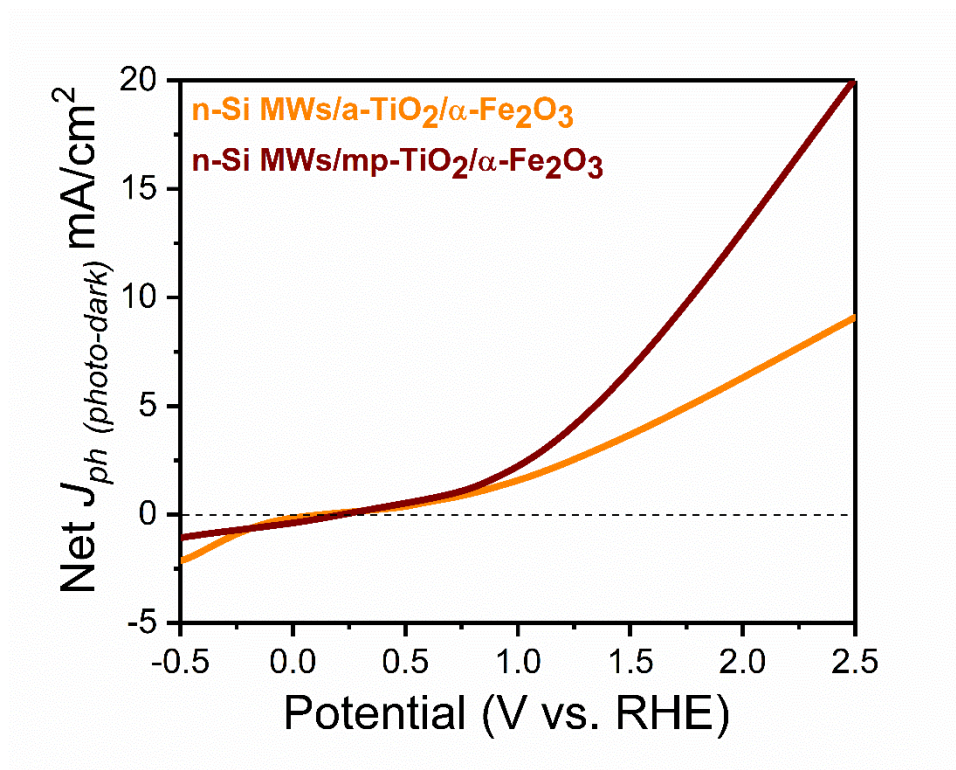
**Figure SI 1:** The SEM image showing the average pore size of mp-TiO<sub>2</sub> as 10 nm.



**Figure SI 2:** XPS spectra for **a)** n-Si MWs/mp-TiO<sub>2</sub>/ α-Fe<sub>2</sub>O<sub>3</sub> with Ti2p<sub>3/2</sub> (binding energy 458.29 ± 0.01 eV) and Ti2p<sub>1/2</sub> (binding energy 464.04 ± 0.01 eV) peaks confirming the Ti<sup>4+</sup> surface species **c)** n-Si MWs/mp-TiO<sub>2</sub>/ α-Fe<sub>2</sub>O<sub>3</sub> with Fe 2p<sub>3/2</sub> (binding energy 711.01 ± 0.01 eV) and Fe 2p<sub>1/2</sub> (binding energy 724.40 ± 0.01 eV) peaks, indicating predominantly α-Fe<sub>2</sub>O<sub>3</sub>.

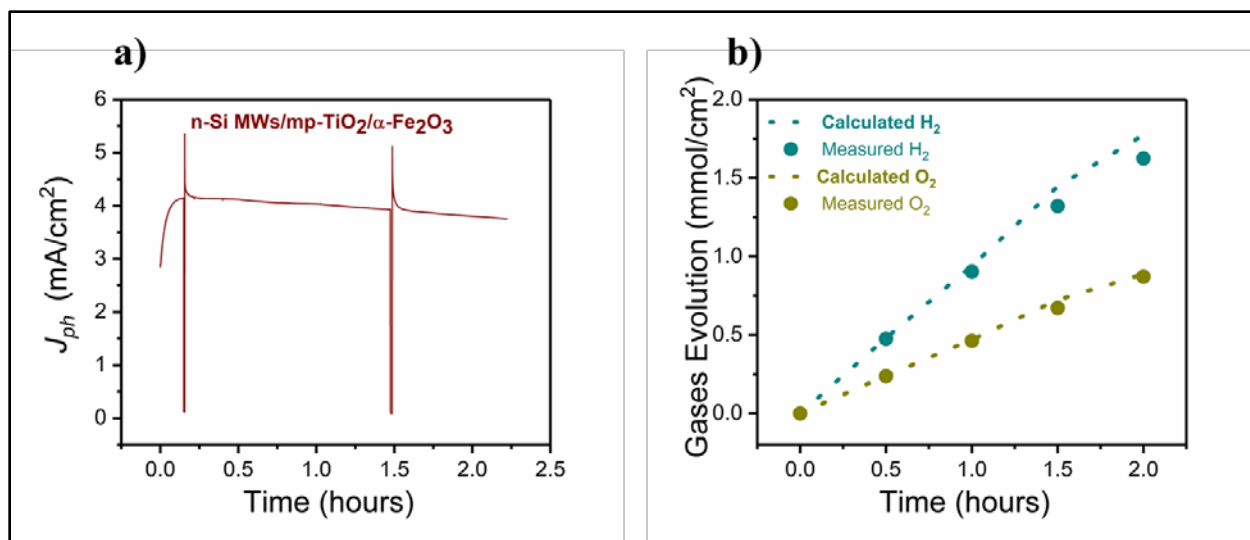


**Figure SI 3:** Linear sweep voltammograms recorded under 1 sun illumination in 1M NaOH (pH 13.9) **a)** planar n-Si, a surface etched n-Si with microwires (n-Si MWs), and functionalized n-Si photo-electrodes, **b)** magnified view of black dashed circle shown in **a)** comparing PEC performance of  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorods grown on n-Si MWs with and without protective TiO<sub>2</sub> interlayer, and **c)** dark current.

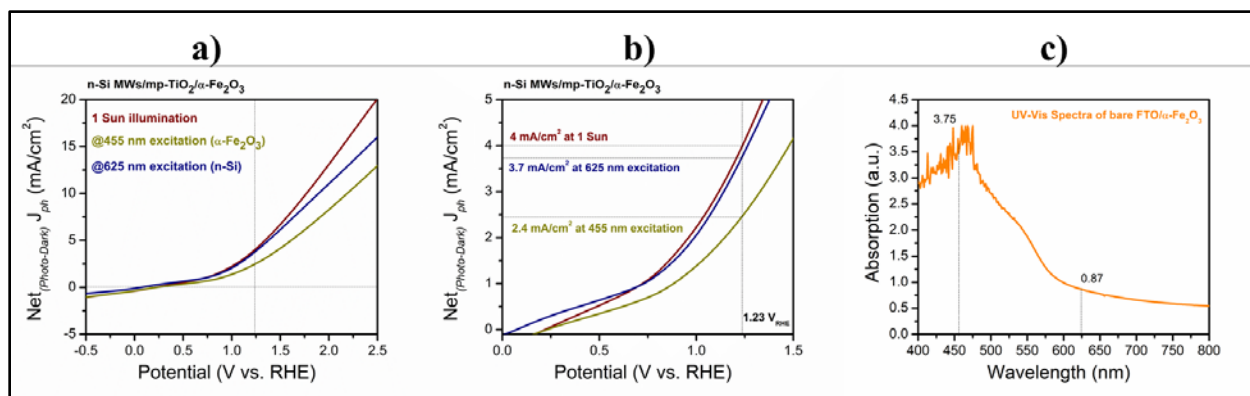


**Figure SI 4:** Linear sweep voltammograms showing significant increase in the  $J_{ph}$  on application of templated mesoporous  $\text{TiO}_2$  protective layer ( $\text{n-Si MWs/mp-TiO}_2/\alpha\text{-Fe}_2\text{O}_3$ ) compared to non-mesoporous amorphous  $\text{TiO}_2$  layer ( $\text{n-Si MWs/a-TiO}_2/\alpha\text{-Fe}_2\text{O}_3$ ).

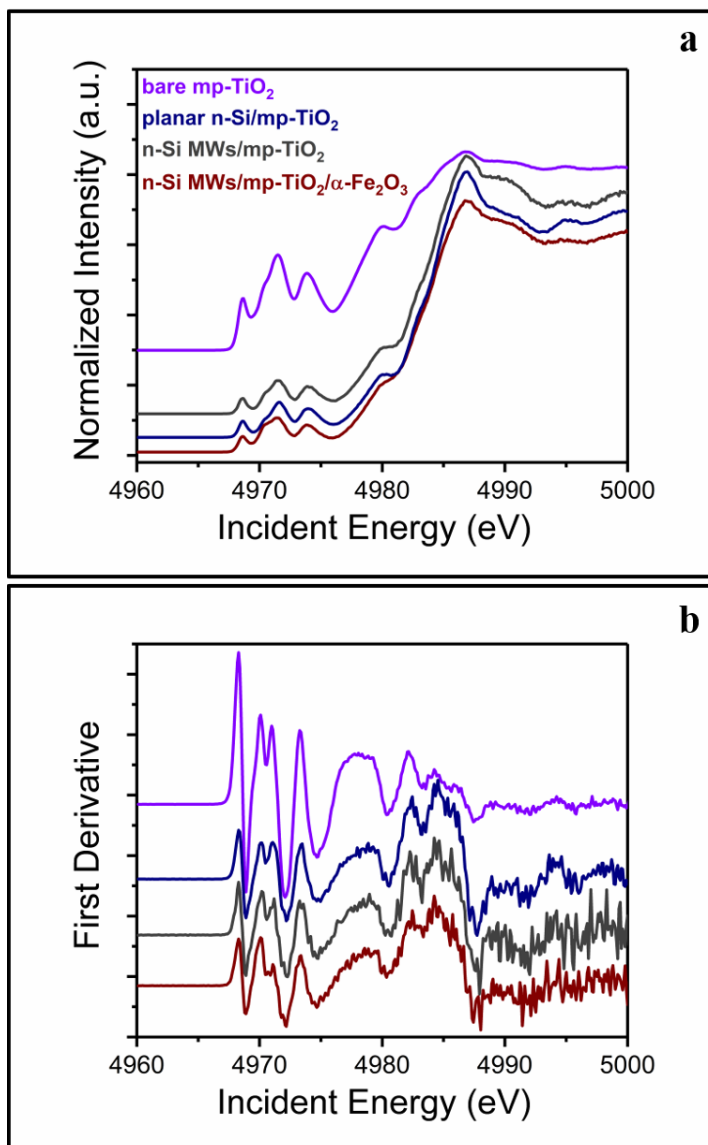




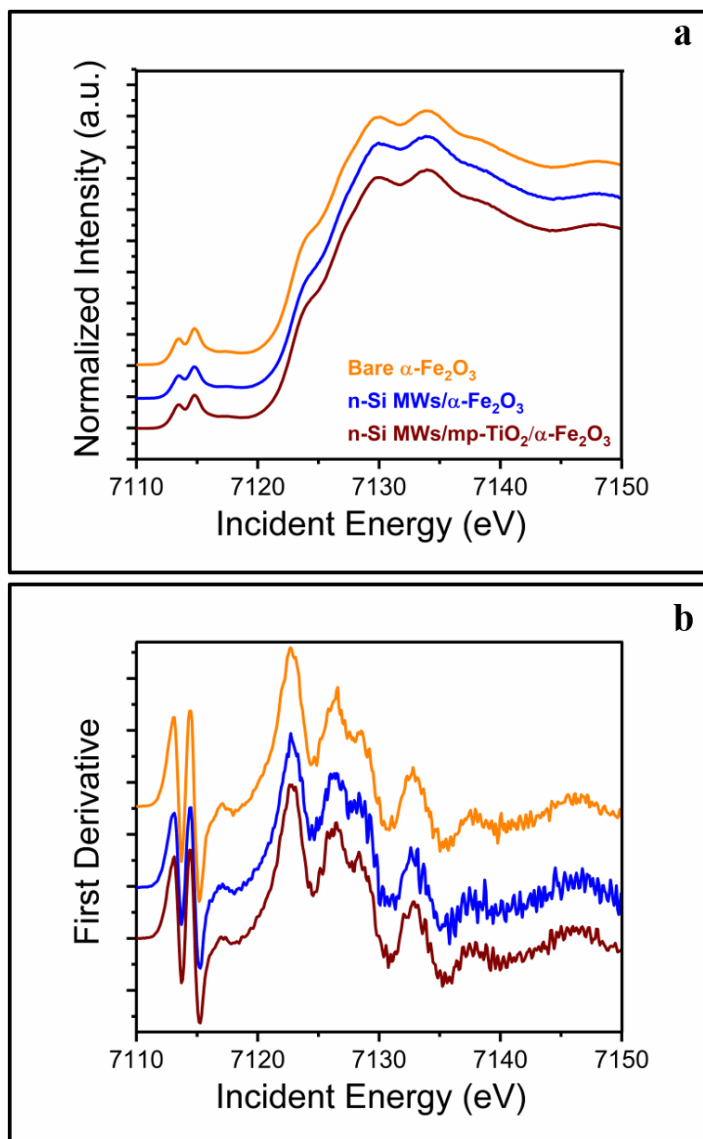
**Figure SI 5:** a) Chronoamperometry measurement performed at constant potential of 1.23  $V_{RHE}$ , b) corresponding photogenerated gases were measured and analyzed using gas chromatography.



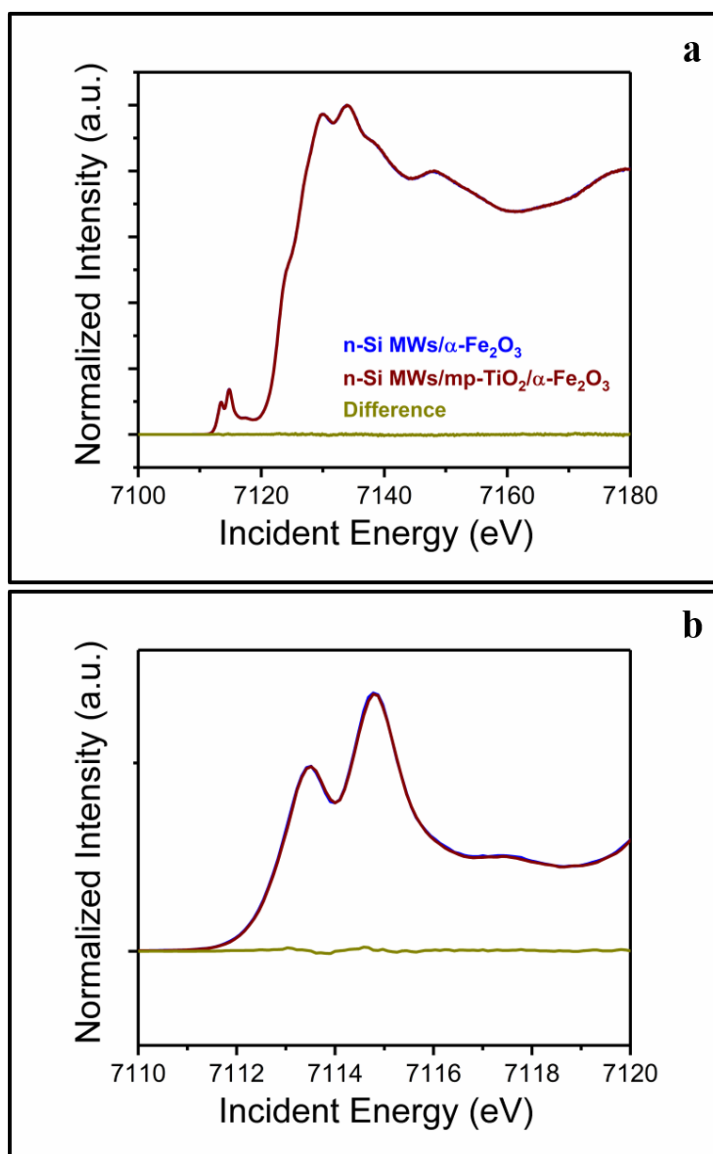
**Figure SI 6:** Linear sweep voltammograms a) and b) indicate that both n-Si MWs and α-Fe<sub>2</sub>O<sub>3</sub> nanorods act as a dual absorber for n-Si MW/mp-TiO<sub>2</sub>/α-Fe<sub>2</sub>O<sub>3</sub> photoelectrode heterogeneous system, and UV-VIS absorption spectra of bare α-Fe<sub>2</sub>O<sub>3</sub> nanorod.



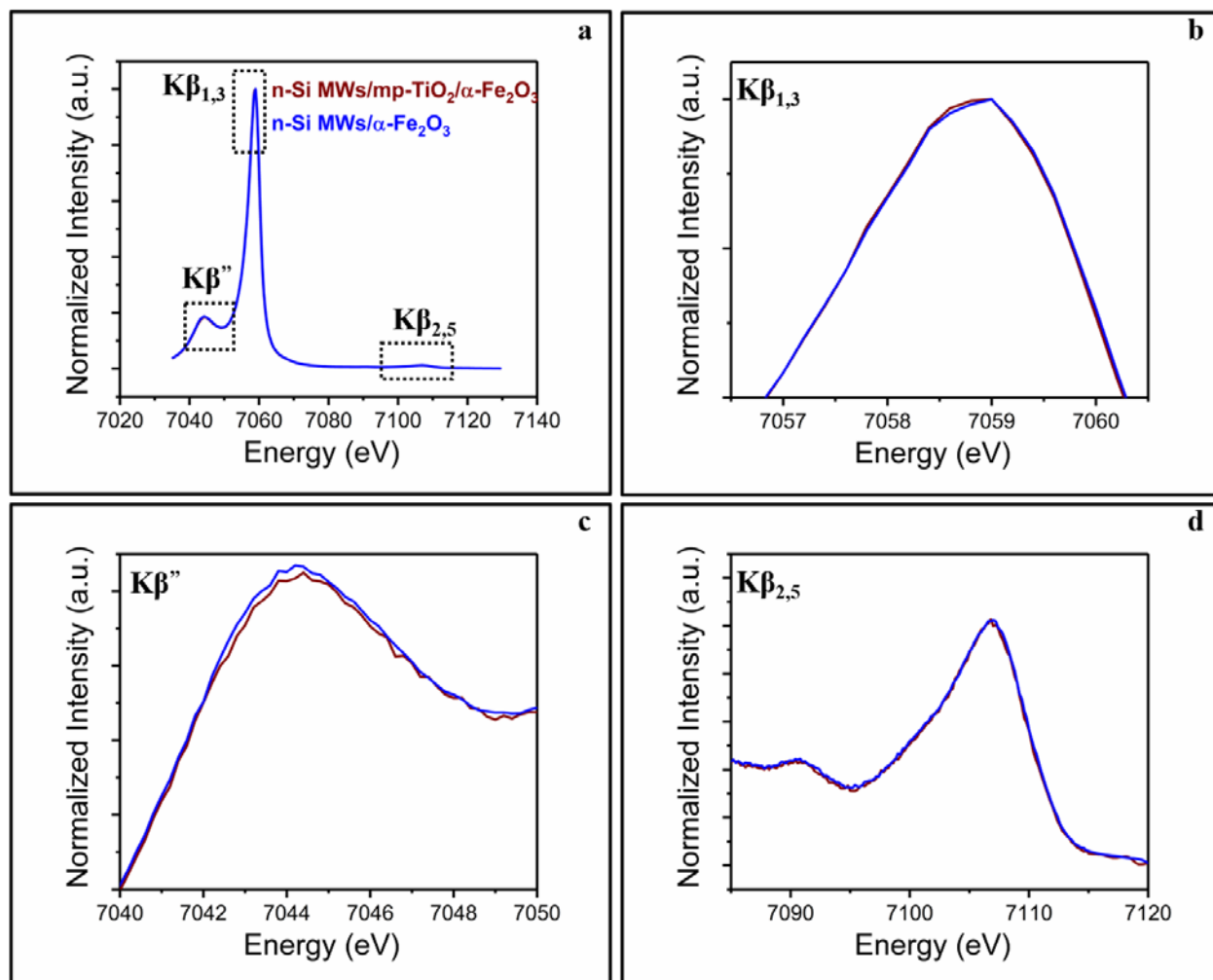
**Figure SI 7:** a) HERFD-XANES and b) first order derivative acquired at the Ti K-edge, for bare mp-TiO<sub>2</sub> as pellet, planar n-Si/mp-TiO<sub>2</sub>, n-Si MWs/ mp-TiO<sub>2</sub> and n-Si MWs/ mp-TiO<sub>2</sub>/α-Fe<sub>2</sub>O<sub>3</sub>.



**Figure SI 8:** a) HERFD-XANES and b) first order derivative acquired at the Fe K-edge, for bare mp-  $\alpha\text{-Fe}_2\text{O}_3$  as pellet, n-Si MWs/  $\alpha\text{-Fe}_2\text{O}_3$  and n-Si MWs/ mp- $\text{TiO}_2$ / $\alpha\text{-Fe}_2\text{O}_3$ .

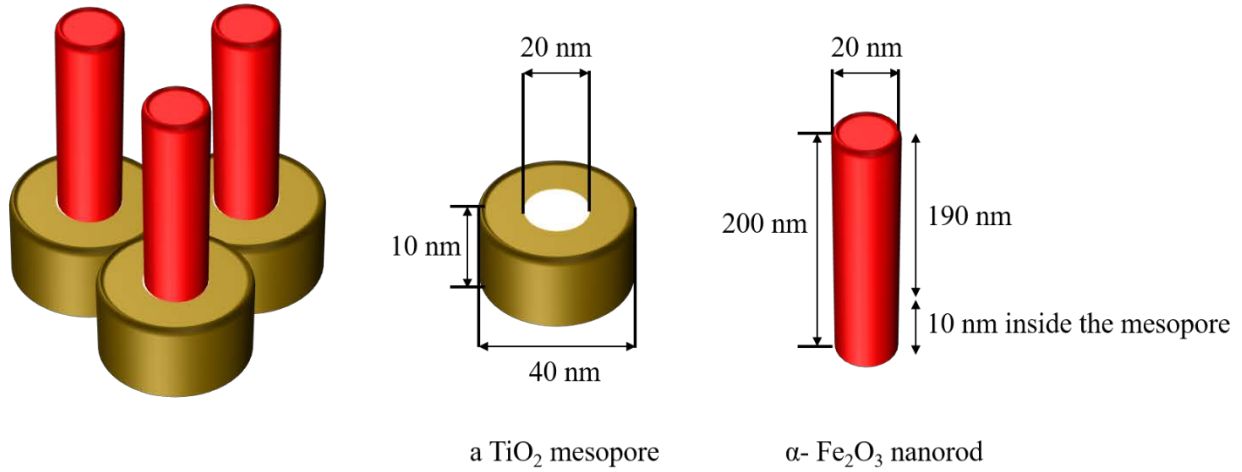


**Figure SI 9:** HERFD-XANES acquired at the Fe K-edge comparing n-Si MWs/  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> and n-Si MWs/ mp-TiO<sub>2</sub>/ $\alpha$ -Fe<sub>2</sub>O<sub>3</sub>. The difference spectrum shows that presence of mp-TiO<sub>2</sub> interlayer do not induce any significant electronic changes in the  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub>.



**Figure SI 10:** Fe K $\beta$  XES spectra acquired for functionalized n-Si MWs photoanodes with **a)** K $\beta$  main and vtc-XES, **b)** K $\beta_{1,3}$ , **c)** K $\beta'$  and **d)** K $\beta_{2,5}$ .

***Approximate estimation of the interfacial contact volume of mp-TiO<sub>2</sub> and  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub>***



**Figure SI 11:** Schematic representation for the dimensions and interaction of mp-TiO<sub>2</sub> with  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorods.

The dimensions of the  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorods are estimated from the SEM image shown in Figure 1.

The dimensions of mp-TiO<sub>2</sub> are estimated from the SEM image reported in our previous study<sup>5, 12</sup> and in the Figure SI 1.

***Fraction of  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> in contact with mp-TiO<sub>2</sub>***

Approximate diameter of  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorod: 20 nm

Approximate depth of a TiO<sub>2</sub> mesopore :10 nm

Approximate length of hematite nanorod inside a mesopore of TiO<sub>2</sub>: 10 nm

Thus, approximately volume of one  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorod inside a mesopore TiO<sub>2</sub> is

**Case 1:** considering whole of  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorod (20 nm diameter, and 10 nm inside mesopore) in contact with mp-TiO<sub>2</sub> inside a mesopore

$$(V = \pi r^2 h) (3.14 \times 10^2 \times 10) = \sim 3142 \text{ nm}^3$$

Total approximate volume of one  $\alpha\text{-Fe}_2\text{O}_3$  nanorod for approximate length of 200 nm is

$$(V = \pi r^2 h) (3.14 \times 10^2 \times 200) = 62831 \text{ nm}^3$$

Fraction of  $\alpha\text{-Fe}_2\text{O}_3$  in contact with  $\text{TiO}_2$  is  $(3142/62831) \times 100 = \sim 4.6 \%$

**Case 2:** considering part of  $\alpha\text{-Fe}_2\text{O}_3$  nanorod in contact with mp- $\text{TiO}_2$  inside a mesopore

$$(V = \pi r^2 h) [3.14 \times (5^2) \times 10] = \sim 785 \text{ nm}^3 \text{ (minimum)}$$

Fraction of  $\alpha\text{-Fe}_2\text{O}_3$  in contact with  $\text{TiO}_2$  is  $(785/62831) \times 100 = \sim 1.2 \%$  (minimum)

***Fraction of mp- $\text{TiO}_2$  in contact with  $\alpha\text{-Fe}_2\text{O}_3$***

Approximate diameter of one mesopore of  $\text{TiO}_2$ : 20nm

Approximate wall thickness of a mesopore of  $\text{TiO}_2$ : 10 nm

Approximate depth of a  $\text{TiO}_2$  mesopore :10 nm

Approximate volume of  $\text{TiO}_2$  around one pore:

**Case 1:** considering complete mesopore of  $\text{TiO}_2$  is in contact with the  $\alpha\text{-Fe}_2\text{O}_3$  nanorod

$$(\text{volume of outer pore} - \text{volume of inner pore}) = (12567 - 3141) = 9426 \text{ nm}^3 \text{ (maximum)}$$

Based on our previous study, the approximate thickness of  $\text{TiO}_2$  around a Si MWs is 50nm, therefore total  $\text{TiO}_2$  content considering 10 nm pores over 50 nm thick  $\text{TiO}_2$  :  $9426 \times 5 = 47130 \text{ nm}^3$

Fraction of  $\text{TiO}_2$  in contact with  $\alpha\text{-Fe}_2\text{O}_3$  is  $(9426/47130) \times 100 = 20 \%$

**Case 2:** considering part of mesopore of TiO<sub>2</sub> in contact with the  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> nanorod

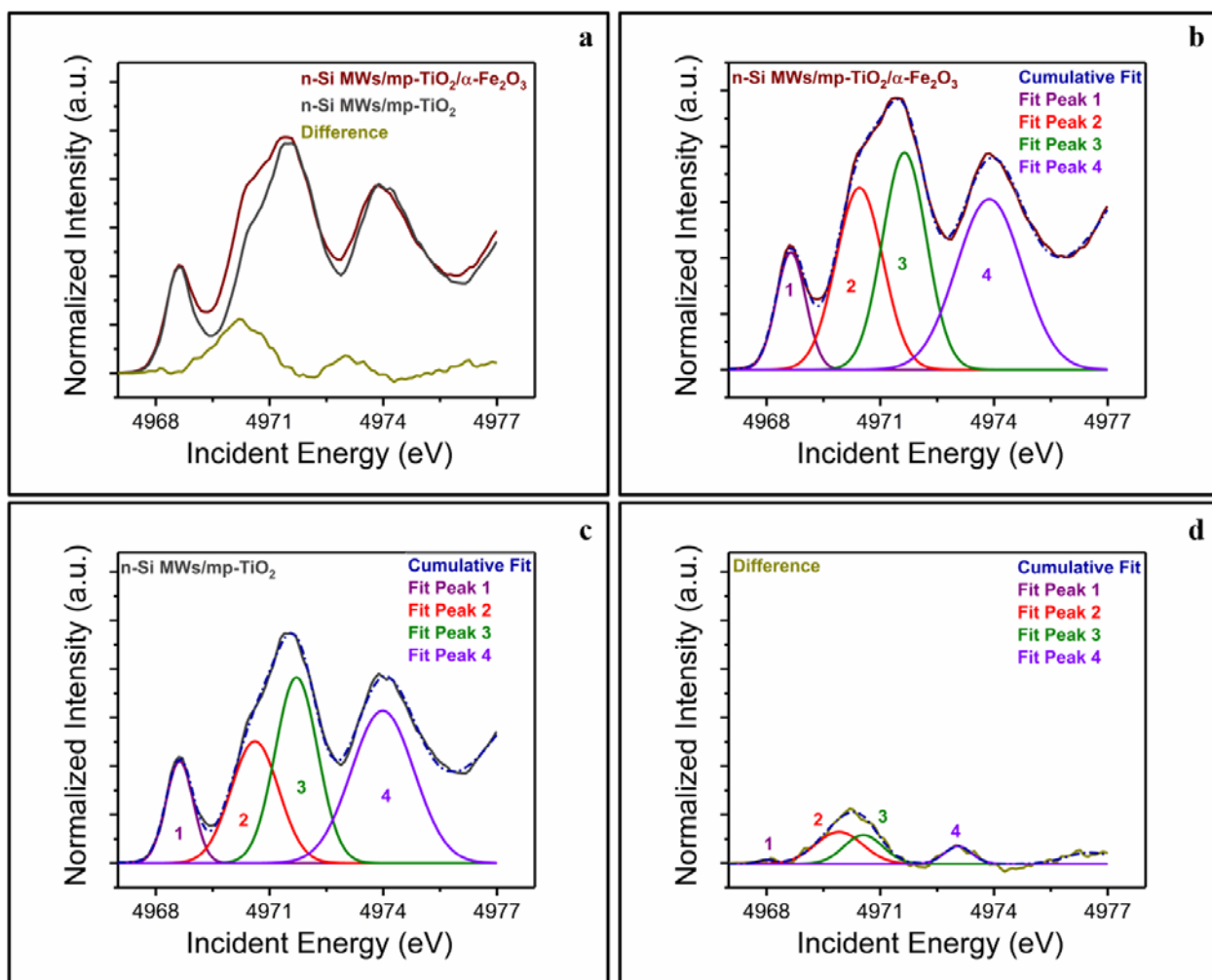
$$(V=\pi r^2 h) [3.14 \times (15^2 - 10^2) \times 10] = \sim 3927 \text{ nm}^3$$

Fraction of TiO<sub>2</sub> in contact with  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> is  $(3927/47130) \times 100 = 8.33 \%$

***Experimental estimation of interfacial contact of mp-TiO<sub>2</sub> and  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub>***

The pre-edge region for n-Si MWs/ mp-TiO<sub>2</sub>/ $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> and n-Si MWs/ mp-TiO<sub>2</sub>, along with the difference spectra, is shown in Figure SI 12 a. The deconvoluted spectra for n-Si MWs/ mp-TiO<sub>2</sub>/ $\alpha$ -Fe<sub>2</sub>O<sub>3</sub>, n-Si MWs/ mp-TiO<sub>2</sub>, and difference spectra are shown in Figure SI 12 b-d, respectively. As the electronic structural change at TiO<sub>2</sub> pre-edge is mainly observed at the pre-edge peak A2 and A2\*, experimental estimation of interfacial contact between mp-TiO<sub>2</sub> and  $\alpha$ -Fe<sub>2</sub>O<sub>3</sub> was assessed by taking the percentage of area in fit peak 2 of Figure SI 12 d (difference spectra) by cumulative area of fit peak 2 and 3 of Figure SI 12 b and c. The area obtained for each peak after deconvolution is given in Table 1.





**Figure SI 12:** a) Pre-edge HERFD-XANES spectra acquired for functionalized  $n\text{-Si MWs}$  photoanodes at the Ti K-edge and deconvoluted spectral peaks for b)  $n\text{-Si MWs/mp-TiO}_2/\alpha\text{-Fe}_2\text{O}_3$  c)  $n\text{-Si MWs/mp-TiO}_2$  and d) difference.

	<b>n-Si MWs/ mp- TiO<sub>2</sub>/α-Fe<sub>2</sub>O<sub>3</sub></b>	<b>n-Si MWs/ mp- TiO<sub>2</sub></b>	<b>Difference</b>	<b>% Change</b>
<b>Peak 1</b>	0.001 ± 2.6E <sup>-5</sup>	9.5E <sup>-4</sup> ± 2.7E <sup>-5</sup>	2.28 E <sup>-5</sup> ± 9.7E <sup>-6</sup>	1.16
<b>Peak 2</b>	0.0026 ± 2.2E <sup>-4</sup>	0.002 ± 3.2E <sup>-4</sup>	5.16 E <sup>-4</sup> ± 0.002	11.21
<b>Peak 3</b>	0.0029 ± 2.28E <sup>-4</sup>	0.0027 ± 3.2E <sup>-4</sup>	3.82 E <sup>-4</sup> ± 0.002	6.82
<b>Peak 4</b>	0.003 ± 1.2E <sup>-4</sup>	0.0033 ± 1.4E <sup>-4</sup>	1.65 E <sup>-4</sup> ± 1.03 E <sup>-5</sup>	2.61
<b>Average</b>	2.38 E <sup>-3</sup>	2.23 E <sup>-3</sup>	2.71 E <sup>-4</sup>	5.45

**Table 1:** Peak area obtained for the deconvoluted peaks shown in Figure SI 12

For example:

The percentage change in the difference spectra considering the area under peaks 2 and 3 can be computed as,

$$\begin{aligned}
 & \frac{\text{Area of Peak2 (difference spectra)}}{\text{Cumulative area of peak 2 and 3 (functionalized Si MWs)}} \times 100 \\
 &= [(5.16 + 3.82) \times 10^{-4}] / (0.0026 + 0.0029 + 0.002 + 0.0027) \times 100 \\
 &= 8.80 \%
 \end{aligned}$$

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